

IN THE CLAIMS:

1-23. (Cancelled)

24. (Original) A method of forming a liquid crystal display device, comprising:

forming a gate line on a substrate, the gate line extending along a first direction and having an opening therein;

forming a first insulating layer on the gate line;

forming a semiconductor layer on the first insulating layer over at least a portion of the opening;

forming a data line on the insulating layer extending along a second direction substantially perpendicular to the first direction, a drain electrode on the semiconductor layer over at least a portion of the opening and, and a source electrode on the semiconductor layer extending from the data line and separated and spaced apart from the drain electrode.

25. (Original) The method of claim 24, further comprising forming a second insulation layer over the semiconductor layer and the source and drain electrodes, the second insulation layer having a drain contact hole that exposes a portion of the drain electrode.

26. (Original) The method of claim 25, further comprising forming a pixel electrode in a pixel region that is defined by an intersection of the gate and data lines, the pixel electrode contacting the drain electrode through the drain contact hole.

27. (Original) The method of claim 24, wherein the opening in the gate line is formed in substantially a "T" shape.

28. (Original) The method of claim 24, wherein the source electrode is formed to substantially surround the drain electrode.

29. (Original) The method of claim 24, wherein the drain electrode is formed in substantially a "T" shape.

30. (Original) The method of claim 24, wherein forming the drain electrode comprises forming a first portion which overlaps the opening and a second portion which overlaps the gate line on at least two opposing sides of the opening.